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Extreme Ultraviolet (EUV) Lithography Market – Global Industry Size, Share, Trends, Opportunity, and Forecast Segmented By Technology Node (7nm and Below, 5nm, 3nm), By Component Type (Light Source (EUV Sources), Mirrors and Optics, Mask and Mask Handling Systems, Others), By End-Use Industry (Semiconductor Manufacturing, Integrated Device Manufacturers (IDMs), Foundries, Memory Manufacturers, Others), By Region & Competition, 2021-2031F

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Abstracts

The Global Extreme Ultraviolet (EUV) Lithography Market will grow from USD 9.34 Billion in 2025 to USD 18.52 Billion by 2031 at a 12.09% CAGR. Extreme Ultraviolet (EUV) Lithography is an advanced semiconductor manufacturing technology that utilizes light with a wavelength of 13.5 nanometers to print intricate circuit patterns on silicon wafers. The market is primarily propelled by the escalating demand for miniaturized, high-performance microchips essential for artificial intelligence, autonomous driving, and next-generation telecommunications.

Key Market Drivers

Surging Demand for High-Performance Computing and Artificial Intelligence Solutions is the primary catalyst accelerating the adoption of Extreme Ultraviolet Lithography, as the computational intensity of generative AI necessitates chip architectures with unprecedented transistor density. Semiconductor manufacturers are rapidly shifting

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production priorities to accommodate AI accelerators and High Bandwidth Memory (HBM), both of which require the precise critical dimensions that only EUV wavelengths can resolve.

Key Market Challenges

The exorbitant capital expenditure and technical complexity associated with EUV systems constitute a significant obstacle impeding the broader expansion of the Global Extreme Ultraviolet Lithography Market. These financial and technical barriers restrict the adoption of this technology to a limited number of well-capitalized semiconductor manufacturers capable of sustaining the massive initial outlay and ongoing operational costs.

Key Market Trends

The Transition to High-Numerical Aperture (High-NA) EUV Systems represents a critical technological evolution designed to overcome the resolution limits of current 0.33 NA tools. By increasing the numerical aperture to 0.55, these next-generation systems allow semiconductor manufacturers to print features with significantly higher contrast and reduced line-edge roughness, thereby eliminating the need for complex and costly double-patterning techniques at sub-2nm nodes.

Key Market Players

ASML Holding NV.

CARL ZEISS AG.

Toppan Photomasks Inc

USHIO, INC

NTT ADVANCED TECHNOLOGY CORPORATION.

KLA CORPORATION

ADVANTEST CORPORATION

Photronics, Inc

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HOYA Corporation

Trumpf

Report Scope:

In this report, the Global Extreme Ultraviolet (EUV) Lithography Market has been segmented into the following categories, in addition to the industry trends which have also been detailed below:

Extreme Ultraviolet (EUV) Lithography Market, By Component Type:

Light Source (EUV Sources)

Mirrors and Optics

Mask and Mask Handling Systems

Others

Extreme Ultraviolet (EUV) Lithography Market, By End-Use Industry:

Semiconductor Manufacturing

Integrated Device Manufacturers (IDMs)

Foundries

Memory Manufacturers

Others

Extreme Ultraviolet (EUV) Lithography Market, By Region:

North America

United States

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- Canada
- Mexico

Europe

- France
- United Kingdom
- Italy
- Germany
- Spain

Asia Pacific

- China
- India
- Japan
- Australia
- South Korea

South America

- Brazil
- Argentina
- Colombia

Middle East & Africa

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South Africa

Saudi Arabia

UAE

Competitive Landscape

Company Profiles: Detailed analysis of the major companies present in the Global Extreme Ultraviolet (EUV) Lithography Market.

Available Customizations:

Global Extreme Ultraviolet (EUV) Lithography Market report with the given market data, TechSci Research offers customizations according to a company's specific needs. The following customization options are available for the report:

Company Information

Detailed analysis and profiling of additional market players (up to five).

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Contents

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6. NORTH AMERICA EXTREME ULTRAVIOLET (EUV) LITHOGRAPHY MARKET OUTLOOK

7. EUROPE EXTREME ULTRAVIOLET (EUV) LITHOGRAPHY MARKET OUTLOOK

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8. ASIA PACIFIC EXTREME ULTRAVIOLET (EUV) LITHOGRAPHY MARKET OUTLOOK

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